

21. The method of claim 18 further comprising pumping on the reaction chamber to maintain flow through the reaction chamber.

→ 22. The method of claim 18 wherein the reactant stream is elongated in a direction along the propagation of the radiation beam.

→ 23. The method of claim 18 wherein the substrate is mounted on a stage that moves relative to a product stream.

→ 24. The method of claim 23 wherein the reactant stream is elongated in a direction along the propagation of the radiation beam to produce a line of product particles that are simultaneously deposited on the substrate and wherein relative movement of the stage sweeps the line across the substrate.

→ 25. The method of claim 23 further comprising moving the substrate from the path of the reactant stream and placing another substrate in the path of the product stream.

→ 26. The method of claim 18 wherein the reactant stream is elongated and wherein a line of light propagates to intersect the elongated reactant stream.

→ 27. The method of claim 18 wherein the reactant inlet moves relative to the substrate such that motion of the reactant inlet sweeps the product particles across the substrate.

→ 28. The method of claim 18 wherein the product stream passes through a conduit prior to reaching the substrate and wherein the conduit moves relative to the substrate with motion of the conduit sweeping the product particles across the substrate.

→ 29. The method of claim 18 wherein an external field is applied to direct the product stream.

→ 30. A method of forming a glass coating comprising heating a particle coating at a temperature and for a period of time sufficient to fuse the particles into a glass and where the particle coating is formed according to the method of claim 18.

31. A method of forming an optical component on a substrate surface, the method comprising removing a portion of a glass coating formed according to the method of claim 30 to form the optical component.

32. The method of claim 31 wherein the removing of a portion of the glass coating is performed by photolithography.

33. A method of coating a substrate comprising:
generating a reactant stream with a cross section perpendicular to the propagation direction characterized by a major axis and a minor axis, the major axis being at least a factor of two greater than the minor axis;
reacting the reactant stream to form a product stream of particles; and
directing the stream of particles to a substrate, wherein flow of the product stream is maintained other than by pumping on the substrate.

34. The method of claim 33 wherein at least about 25 grams per hour are deposited onto the substrate.

35. The method of claim 33 wherein the reaction is driven by a light beam.

36. The method of claim 33 wherein the major axis is at least a factor of ten greater than the minor axis.

37. The method of claim 33 wherein the flow of the stream of particles is maintained by momentum of the product stream.

38. The method of claim 33 wherein the flow of the stream of particles is maintained by pumping out a chamber and wherein the substrate is located within the chamber.

39. (Amended) A method of coating a substrate having a diameter greater than about 5 cm, the method comprising:

reacting a reactant stream to form a product stream comprising product particles, wherein the particles are produced by the reaction; and

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depositing simultaneously a stream of particles over the entire surface of the substrate and wherein at least about 5 grams per hour of particles are deposited onto the substrate.

40. The method of claim 39 wherein the product stream of particles is defocused with an external field.

41. The method of claim 40 wherein the external field is generated by thermal gradient generator or an electric field generator.

42. A method of coating a substrate comprising:
simultaneously generating multiple product streams by chemical reaction driven by a light beam; and
depositing the multiple product streams simultaneously on a moving substrate at sequential locations on the substrate.

Please add new claims 43-61 as follows:

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43. (New) The method of claim 18 wherein the reactant stream comprises a silicon precursor.

44. (New) The method of claim 18 wherein the reactant stream comprises a metal precursor.

45. (New) The method of claim 33 wherein the reactant stream comprises a silicon precursor.

46. (New) The method of claim 33 wherein the reactant stream comprises a metal precursor.

47. (New) The method of claim 35 wherein the light beam comprises infrared light.

48. (New) The method of claim 33 wherein the substrate is moved relative to the product stream while directing the stream of particles to the substrate to coat different portions of the substrate.

49. (New) The method of claim 33 wherein the substrate is moved relative to the product stream while directing the stream of particles to the substrate to coat the surface of the substrate in one pass of the substrate through the product stream.

50. (New) The method of claim 39 wherein at least about 25 grams per hour are deposited onto the substrate.

51. (New) The method of claim 39 wherein the reaction is driven by energy from a radiation beam.

52. (New) The method of claim 39 wherein the reactant stream comprises a silicon precursor.

53. (New) The method of claim 42 wherein at least two of the multiple product streams comprise product particles with the same composition.

54. (New) The method of claim 42 wherein at least one of the multiple product streams comprise product particles with a different composition from product particle in another of the multiple product streams.

55. (New) A method of coating a surface of a substrate, the method comprising:
reacting a reactant stream to product a product stream comprising particles wherein the particles are produced by the reaction; and
directing the product stream to the substrate to deposit at least about 5 grams per hour onto the substrate.

56. (New) The method of claim 56 wherein the reaction is driven by energy from a radiation beam.